

RECEIVED
CENTRAL FAX CENTER

MAY 16 2006

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the PATENT APPLICATION of:

Ching-Wei Lin

Application No.: 10/767,665

Confirmation No.: 5412

Filed: January 29, 2004

For: PROCESS FOR FORMING
POLYCRYSTALLINE SILICON LAYER BY
LASER CRYSTALLIZATION

Group: 2813

Examiner: Stephen W. Smoot

Our File: TET-PT049

Date: May 16, 2006

REPLY PURSUANT TO 37 C.F.R. § 1.116

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This Reply is being timely filed in response to the February 17, 2006 Office
Action.

Please amend the application without prejudice or disclaimer as follows.

BEST AVAILABLE COPY